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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/688,851	10/17/2003	Tim Pinkerton	10559-861001/P17309	9464
20985	7590	12/20/2005	EXAMINER	
FISH & RICHARDSON, PC P.O. BOX 1022 MINNEAPOLIS, MN 55440-1022			ROSASCO, STEPHEN D	
			ART UNIT	PAPER NUMBER
			1756	
DATE MAILED: 12/20/2005				

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

10/688,851

Applicant(s)

PINKERTON ET AL.

Examiner

Stephen Rosasco

Art Unit

1756

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 11 July 2005.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-23 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-23 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 10/17/03 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
- ☐ Certified copies of the priority documents have been received.
 - ☐ Certified copies of the priority documents have been received in Application No. _____.
 - ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- ☒ Notice of References Cited (PTO-892)
- ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____
- ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date _____
- ☐ Notice of Informal Patent Application (PTO-152)
- ☐ Other: _____

Detailed Action

In response to the communication of 7/11/05 the examiner withdraws the prior office action rejection and includes a new rejection based on newly cited art.

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-23 are rejected under 35 U.S.C. 102(e) as being anticipated by Butt et al. (US 2004/0131950 A1).

The claimed invention is directed to an apparatus comprising: a plurality of features, the features including a plurality of primary features in a primary feature region, each primary feature abutting at least one other primary feature, and a plurality of sub resolution features in a boundary region surrounding the primary feature region.

And wherein there is no opaque material between adjacent features in the primary feature region or the boundary region.

And wherein each of the primary features has a size operative to resolve at an imaging plane at a resolution, and wherein each of the sub resolution features has a size operative not to resolve at the imaging plane at said resolution.

And wherein each of a plurality of pairs of abutting features in the primary feature region and the boundary region have different phase step heights, said abutting features including primary features and sub resolution features.

Butt et al. teach a mask for projecting a structure pattern onto a semiconductor substrate in an exposure unit, the exposure unit having a minimum resolution limit for projecting the structure pattern onto the semiconductor substrate, the mask comprising: a substrate;

at least one raised first structure element on said substrate, said first structure element having a lateral extent amounting to at least the minimum resolution limit; a configuration of raised second structure elements, said second structure elements: being disposed in a vicinity of said first structure element on said substrate and arranged in a matrix with a row spacing and a column spacing; having a substantially identical shape and size;

and having a respective lateral extent less than the minimum resolution limit, so that the structure configuration cannot be transferred to a photosensitive resist layer formed on the semiconductor substrate.

And wherein said at least one raised first structure element is surrounded by said matrix of said second structure elements.

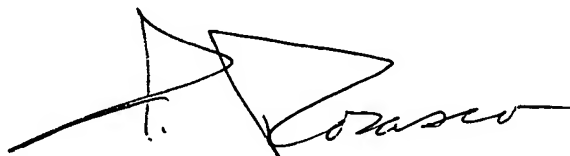
Butt et al. also teach in section [0011] Another solution involves arranging "sublithographic structures" (subresolution assist features (SRAF)) in the immediate surroundings of the isolated structure elements on the mask. These sublithographic structure elements have a lateral extent which is smaller than the minimum lateral extent which can be attained with the exposure unit. They are thus not mapped on the semiconductor substrate under normal exposure conditions. Their proximity to the isolated structure means that the sublithographic structure element delivers a light and phase contribution to the mapping of the isolated structure, however, similarly to the way in which this would bring about adjacent structure elements within a dense structure configuration, for example. The sublithographic structure elements therefore simulate a dense structure configuration around the isolated structure element.

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Conclusion

Any inquiry concerning this communication or earlier communications from the Examiner should be directed to Stephen Rosasco whose telephone number is (571) 272-1389. The Examiner can normally be reached Monday-Friday, from 8:00 AM to 4:30 PM. The Examiner's supervisor, Mark Huff, can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

A handwritten signature in black ink, appearing to read 'S. Rosasco', with a stylized, sweeping flourish extending from the end of the name.

S. Rosasco
Primary Examiner
Art Unit 1756

S. Rosasco
12/14/05